

a second atomic layer doping region for diffusing said first dopant species in
said first substrate, said first and second doping regions being chemically isolated
from one another by an inert gas curtain; and

a loading assembly for moving said first substrate from said first doping
region to said second doping region, thereby enabling deposition of a first atomic
monolayer in said first doping region, followed by diffusion of said first atomic
monolayer in said second doping region.

Cut

2